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Molecular Crystals and Liquid Crystals Science and Technology. Section A. Molecular Crystals and Liquid Crystals

Publication details, including instructions for authors and subscription information:

<http://www.tandfonline.com/loi/gmcl19>

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Version of record first published: 24 Sep 2006

To cite this article: Nan Lu, Ran Lu, Ce Wang, Changsheng Cao, Yunwei Cao, Xinming Qian, Xiangdong Chai, Yubai Bai & Tiejin Li (1999): Electrical Property of a Layered Non-Centrosymmetric Self-Assembly Based on Barbituric Acid and Melamine Derivatives, *Molecular Crystals and Liquid Crystals Science and Technology. Section A. Molecular Crystals and Liquid Crystals*, 337:1, 173-176

To link to this article: <http://dx.doi.org/10.1080/10587259908023405>

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Electrical Property of a Layered Non-Centrosymmetric Self-Assembly Based on Barbituric Acid and Melamine Derivatives

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Electrical property of a layered non-centrosymmetric self-assembly $PB_{12} \cdot M_{12}$ was studied. The assembly was fabricated by hydrogen bonding interaction of 5-(4-dodecyloxy benzylidene)-2,4,6-(1H,3H)-pyrimidinetrione (PB_{12}) and 4-amino-2,6-didodecylamine-1,3,5-triazine (M_{12}). The result shows that the assembly has a good electrical insulation ability.

Keywords: electrical property; self-assembly; barbituric acid; melamine

INTRODUCTION

Non-centrosymmetric organic crystals formed by supramolecular self-assembling are getting more and more important, due to their potential applications in functional materials, such as microelectronic devices and high-density information storage materials^[1]. It appears that self-assemblies constructed through hydrogen bonds are superior in many properties to those through other non-covalent interactions, since hydrogen bonds are able to cause a stronger interaction between molecules and provide the assemblies with a better orientation ability of molecules^[2-6]. One of typical examples is the assemblies composed of barbituric acid and melamine

derivatives, which bear complementary hydrogen bond groups. There have been a number of reports concerning this kind of assemblies in its assembling processes and structure analysis^[7-9]. However, their electrical properties have not been investigated yet. In this work, we represent the capacitance-voltage (*C-V*) feature of a layered non-centrosymmetric self-assembly $PB_{12}M_{12}$, which is constructed by 5-(4-dodecyloxy benzylidene)-2,4,6-(1H,3H)-pyrimidinetrione (PB_{12}) and 4-amino-2,6-didodecylamine-1,3,5-triazine (M_{12}). Their molecular structures are shown in Figure 1.

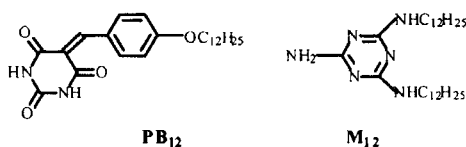


FIGURE 1. Molecular structures of PB_{12} and M_{12}

EXPERIMENTAL

PB_{12} and M_{12} were synthesized in our laboratory^[10]. Chloroform was purchased from Tianjin Chemicals Factory and treated by refluxing it overnight by the presence of P_2O_5 under argon.

PB_{12} and M_{12} were assembled according to a method reported in detail elsewhere^[7]. For *C-V* measurement, a chloroform suspension of the solid assembly was spread on a n-type silicon wafer with a thin layer of silica. After chloroform was evaporated, an aluminum dot as top electrode was coated on the surface of the assembly by vacuum deposition technique to achieve a device $Al/PB_{12}M_{12}/n$ -silicon. For comparison, $Al/SiO_2/n$ -silicon was also built up, where the SiO_2 layer is from the n-silicon surface. *C-V* curves for the two devices were recorded on a PAR MODEL 410 C-V

plotter at 1 MHz with the scanning rates of 5 mV/s and 10 mV/s.

RESULTS AND DISCUSSION

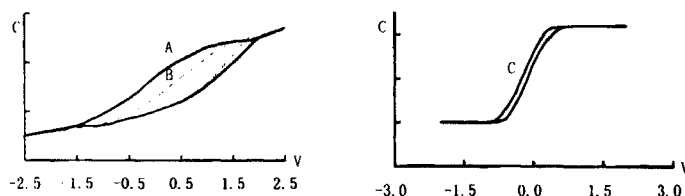


FIGURE 2. C - V curves of $PB_{12}M_{12}$ assembly (scanning rate of A: 5 mV/s, B: 10 mV/s) and silica for comparison (scanning rate of C: 5 mV/s)

Figure 2 shows the C - V measurement results of the devices with $PB_{12}M_{12}$ and silica layer. Curves A and B represent changes in capacitance of $PB_{12}M_{12}$ with bias at scanning rates of 5 mV/s and 10 mV/s, and curve C corresponds a change in capacitance of silica layer with bias at 5 mV/s. By comparison, it is found that there is a larger shift in C - V curves A and B than in curve C, that is, $PB_{12}M_{12}$ leads to a larger hysteresis than the silica layer does. With the increase in the scanning rate from 5 mV/s to 10 mV/s, the hysteresis caused by $PB_{12}M_{12}$ becomes weaker.

A possible explanation for the hysteresis can be assigned to the retaining of electrons in the silica layer and $PB_{12}M_{12}$ assembly. Under an applied field, electrons are capable of injecting into the SiO_2 layer in device Al/ SiO_2 /n-Si and into the assembly $PB_{12}M_{12}$ and also the silica layer in the device Al/ $PB_{12}M_{12}$ /n-silicon. Furthermore, much more electrons are retained in the assembly. Then a built-in electronic field E' is set up which opposes the applied field E . This means that the assembly $PB_{12}M_{12}$ is a better insulator than silica. Therefore, the device Al/ $PB_{12}M_{12}$ /n-silicon can be thought of as a typical metal-insulator-semiconductor [MIS] structure, and

Al/SiO₂/n-silicon just as a typical metal/oxide/semiconductor [MOS] structure.

Additionally, the magnitude of the hysteresis for PB₁₂M₁₂ directly changes with scanning rate. The slower the scanning rate is, the larger the hysteresis is. This could be attributed to the position of electrons in the layered assembly. At a lower scanning speed the electrons can be located in the deeper layer of the assembly and a stronger built-in field is set up, so a larger hysteresis can be observed. Therefore, the hysteresis in curve A is larger than one in curve B, which were achieved at 5 mV/s and 10 mV/s, respectively. The result shows that the assembly might be used in functional materials, and more detailed studies on this system are now in progress.

Acknowledgments

This work was supported by the National Climbing B Project and the NSFC.

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